EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2803	substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:16
L2	670	L1 and polarity	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:16
L3	144	L2 and solubility	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:16
L4	2803	substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:23
L5	61	L4 and (acid near3 generator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:23
L6	53	L5 and pattern$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:23
L7	1652	(438/29).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:25

L8	15	L7 and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:25
L9	1736	(438/48).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:27
L10	6	L9 and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:27
L11	68	L9 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:27
L12	6	L11 and polarity	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:28
L13	2	L11 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:28
L14	413	(438/82).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:29
L15	35	L14 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:29

L16	3	L15 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:30
L17	50	(438/148).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:30
L18	502	(438/636).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:31
L19	20	L18 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:31
L20	290	(438/671).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:32
L21	25	L20 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:32
L22	512	(438/717).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:34
L23	27	L22 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:34

L24	2	L23 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:34
L25	1278	(438/725).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:35
L26	77	L25 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:35
L27	3	L26 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:35
L28	95	(430/58.3).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:43
L29	198	(430/58.6).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:44
L30	50	L29 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:44
L31	0	L30 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:45

L32	250	(430/59.5).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:46
L33	86	L32 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:46
L34	0	L33 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:46
L35	971	(430/60).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:47
L36	317	L35 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:48
L37	3	L36 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:48
L38	762	(430/73).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:49
L39	205	L38 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:49

L40	0	L39 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:49
L41	36	L39 and solubility	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:50
L42	711	(430/76).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:51
L43	193	L42 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:51
L44	0	L43 and polarity and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:51
L45	38	L43 and polarity	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:52
L46	905	(430/83).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:54
L47	209	L46 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:54

L48	39	L47 and polarity	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:54
L49	315	substrate and (photosensitive near2 (layer or film)) and polarity and gate and acid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:56
L50	91	L49 and alkali	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:56
L51	1518	(438/758).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/09/08 12:57
L52	23	L51 and substrate and (photosensitive near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/09/08 12:58
S1	2665	substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 15:43
S2	1	S1 and (polarity near2 change near2 reaction)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 15:44
S3	632	S1 and polarity	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 15:46

S4	138	S3 and solubility	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 15:46
S5	102	S4 and developer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 15:46
S6	23	S5 and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 15:47
S7	2	("6197473").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:02
S8	2	("20020081501").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:11
S9	2	("2000352821").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:17
S10	1698	(438/199).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:22
S11	1	S10 and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:22

S12	1	S10 and substrate and (photosensitive near4 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:23
S13	1352	(430/108.1).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:27
S14	15	S13 and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:27
S15	8	S14 and pattern$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:28
S16	2	S14 and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:31
S17	866	(430/108.3).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:31
S18	17	S17 and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:31
S19	9	S18 and pattern$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:31

S20	6	S18 and gate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:32
S21	750	(430/108.7).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2009/03/20 16:33
S22	0	"L121" and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:33
S23	19	S21 and substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:33
S24	7	S23 and pattern$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 16:33
S25	1	(damacin near2 wiring near2 pattern)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 20:32
S26	2665	substrate and (photosensitive near2 organic near2 (layer or film))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 21:07
S27	59	S26 and (acid near3 generator)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/03/20 21:07

| S28 | 53 | S27 and pattern$4 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/03/20 21:08 |

EAST Search History (Interference)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L53	1	substrate and (photosensitive near2 (layer or film)) and polarity and gate and acid and alkali.clm.	USPAT; UPAD	OR	ON	2009/09/08 13:01
L54	15	substrate and (photosensitive near2 (layer or film)) and polarity and gate and acid.clm.	USPAT; UPAD	OR	ON	2009/09/08 13:01

9/8/2009 1:03:38 PM
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